

	Hits	Search Text	DBs	Time Stamp
1	2728	basic with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide))	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:54
2	158	basic with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive)	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:48
3	6026	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide))	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:55
4	121	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) same (photoresist resist photosensitive)	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:55
5	1	basic with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (foot feet lateral) same (photoresist resist photosensitive)	US -PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:46

	Hits	Search Text	DBs	Time Stamp
6	8	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (foot feet lateral) same (photoresist resist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:47
7	4	basic with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive) same ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (foot feet)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:48
8	55	basic with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive) and ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) with substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:49

	Hits	Search Text	DBs	Time Stamp
9	60	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) same (photoresist resist photosensitive) and ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) with substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:50
10	3	basic adj (fluid liquid) with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:54
11	304	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:01
12	200	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive) and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:56

	Hits	Search Text	DBs	Time Stamp
13	60	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (treat treating treatment treated) near5 ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive) and substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:56
14	19	basic near5 (treat treating treatment treated) near5 ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 16:59
15	19	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine (basic adj (liquid fluid))) near5 (treat treating treatment treated) near5 ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) with substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:03

	Hits	Search Text	DBs	Time Stamp
16	89	basic with (treat treating treatment treated) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (photoresist resist photosensitive) same ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:07
17	35	photoresist same substrate and (treat treating treated) near5 basic same (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and photoresist with (pattern patterning patterned develop developing developed)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:15
18	37	photoresist same substrate and (treat treating treated) near5 basic same (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (resist photosensitive photoresist) with (pattern patterning patterned develop developing developed)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:18

	Hits	Search Text	DBs	Time Stamp
19	52	(treat treating treated) near5 basic with (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide)) and (resist photosensitive photoresist) with (pattern patterning patterned develop developing developed) and (resist photoresist photosensitive) same substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:24
20	2	"20050054216"	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:23
21	791	(treat treating treated) near5 basic with (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:24
22	791	(treat treating treated) near5 basic with (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:25
23	204727	(treat treating treated) near5 basic (fluid liquid) near5 (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:25

	Hits	Search Text	DBs	Time Stamp
24	1	(treat treating treated) near5 basic adj (fluid liquid) near5 (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) and substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:26
25	370	(treat treating treated) near5 (KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) and substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:26
26	15844	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (substrate (silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) and substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:26
27	4558	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (substrate ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film)) and substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:27
28	916	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (substrate ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film)) and substrate and (resist photoresist photosensitive)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:27

	Hits	Search Text	DBs	Time Stamp
29	787	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (substrate ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film) with substrate) and substrate and (resist photoresist photosensitive)	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:29
30	468	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (substrate ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film) with substrate) and substrate and (resist photoresist photosensitive) with (substrate ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:31
31	23	(treat treating treated) near5 (KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (substrate ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film) with substrate) and substrate and (resist photoresist photosensitive) with (substrate ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:34

	Hits	Search Text	DBs	Time Stamp
32	0	(treat treating treated) near5 (KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film) with substrate) and substrate and (resist photoresist photosensitive) with (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:35
33	0	(treat treating treated) near5 (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film) with substrate) and substrate and (resist photoresist photosensitive) with (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:37

	Hits	Search Text	DBs	Time Stamp
34	1	(treat treating treated) with (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) with (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film) with substrate) and substrate and (resist photoresist photosensitive) with (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:35
35	0	(treat treating treated) near5 (KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film) with substrate) and substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:36
36	18	(treat treating treated) near5 (KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film)) and substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:37
37	954	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film)) and substrate	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:40

	Hits	Search Text	DBs	Time Stamp
38	87	(basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film)) and substrate and (resist photoresist photosensitive) with ((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film))	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:37
39	39	(KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) adj (layer film)) and substrate not acid	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:48
40	10	substrate and (treat treating treated) with basic and antireflective adj coating	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:46
41	13	substrate and (treat treating treated) with (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) and antireflective adj coating	US - PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:48

	Hits	Search Text	DBs	Time Stamp
42	263	substrate and (treat treating treated) with (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) and (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film) with substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:48
43	145	substrate and (treat treating treated) with (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) and (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film) with substrate) and (resist photoresist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:48
44	53	substrate and (treat treating treated) near3 (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) and (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film) with substrate) and (resist photoresist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:49

	Hits	Search Text	DBs	Time Stamp
45	3	substrate and (treat treating treated) near3 (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film) with substrate) and (resist photoresist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:51
46	3	substrate and (treat treating treated) near3 (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film) with substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:50
47	354	substrate and (treat treating treated) near3 (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:55
48	35	substrate and (treat treating treated) near3 (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film)) and (resist photoresist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:53

	Hits	Search Text	DBs	Time Stamp
49	72	substrate and (treat treating treated) with (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film)) and (resist photoresist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:55
50	20	substrate and (treat treating treated) with (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) with (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film)) and (resist photoresist photosensitive)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:53
51	85	substrate and (treat treating treated) near3 (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film)) not (vapor gas)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:55

	Hits	Search Text	DBs	Time Stamp
52	25	substrate and (treat treating treated) with (basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film)) and (resist photoresist photosensitive) not (vapor gas)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:57
53	3	substrate and (treat treating treated) with ((basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine) near5 (fluid liquid)) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:59
54	9	substrate and (treat treating treated) with ((basic KON NaOH (NH?sub?4F NH?sub?4 adj F) alkylamine amine)) with (liquid fluid) same (((silicon adj oxide) (silicon adj nitride) organic (silicon adj carbide) anti?reflective) near4 (layer film))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	2005/12/11 17:59